



PATENT ABSTRACTS OF JAPAN

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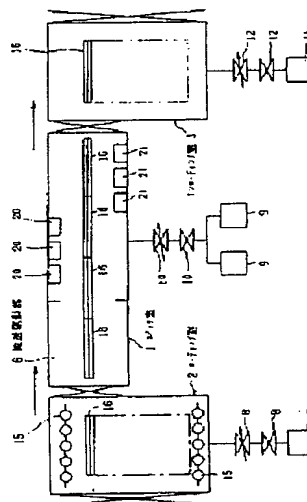
(54) SPUTTERING APPARATUS

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(57) Abstract:

PURPOSE: To clean the surface of base plate at low temp. and in short time to improve the adhesive force of film by irradiating the surface of a base plate with ultraviolet rays in an evacuable loading chamber connected to a sputtering chamber.

CONSTITUTION: The base plates set on trays 16 in the loading chamber 2 evacuated with a cryopump 7 are transported into the sputtering chamber 1 evacuated by a cryopump 7. In this case, films are formed on the base plates by sputtering targets 20, 21 while the trays 16 are carried by a carrying and driving part 6. Then the trays 16 are carried into an unloading chamber 3 evacuated by a cryopump 11 and then taken out. In the above mentioned sputtering apparatus, an ultraviolet ray irradiation unit is disposed in the loading chamber 2, and the ultraviolet rays from ultraviolet ray lamps 15 irradiates the surfaces of base plates. By this method, the surface of base plate is efficiently cleaned in a short time with a small-sized equipment, and the film of high adhesive force is formed.



Spent at home 6 "x" 10...

Remise, on y travaille. Beau plan à l'achèvement ?

Dependence on Sp. Heterom. 7